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ABSTRACT

POLISHING COMPOSITION AND POLISHING METHOD

A polishing composition includes more than 0.1% by mass of colloidal silica, and water, and has a pH of 6 or less.

- 5 The polishing composition has the ability to polish a titanium material at a high stock removal rate. Thus, the polishing composition is suitable for use in applications for polishing a titanium-containing object.

Fig. 2



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